

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

ATTORNEY DOCKET NO. 025311-0111

Applicant: Tetsuro HANAWA
Title: PROJECTION ALIGNER, EXPOSING METHOD AND SEMICONDUCTOR DEVICE
Appl. No.: Unassigned
Filing Date: 11/08/2001
Examiner: Unassigned
Art Unit: Unassigned

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to examination of the above-identified application, Applicant respectfully requests that the following amendments be entered into the application:

IN THE CLAIMS:

In accordance with 37 C.F.R. §1.121, please substitute for original claims 18 and 20 the following rewritten version of the same claims, as amended. The change is shown explicitly in the attached "Version with Markings to Show Changes Made."

18. (Amended) The projection exposure method according to claim 10, wherein, in said second step, said substrate is irradiated with exposure light of said appropriate intensity by changing an interval between pulse light emissions of said exposure light.

20. (Amended) A semiconductor device fabricated by use of the projection exposure method according to claim 10.

Appl. No. Unassigned

REMARKS

Applicant respectfully requests that the foregoing amendments to Claims 18 and 20 be made prior to examination of the present application.

Respectfully submitted,

November 8, 2001

Date

FOLEY & LARDNER

Customer Number: 22428



22428

PATENT TRADEMARK OFFICE

Telephone: (202) 672-5485

Facsimile: (202) 672-5399

William T. Ellis

Attorney for Applicant

Registration No. 26,874

VERSION WITH MARKINGS TO SHOW CHANGES MADE

18. (Amended) The projection exposure method [as claimed in any one of claims 10 to 16] according to claim 10, wherein, in said second step, said substrate is irradiated with exposure light of said appropriate intensity by changing an interval between pulse light emissions of said exposure light.

20. (Amended) A semiconductor device fabricated by use of the projection exposure method according to claim[s] 10.